Supplementary Information

Direct Characterization of the Doping State of Graphene Layer in Organic Semiconductor Electrode Structure by *in-situ* Photoemission Spectroscopy Analysis with Ar Gas Cluster Ion Beam Sputtering

Dong-Jin Yun^a, Seyun Kim^b, Chang Hoon Chung^a, Chang Seok Lee^a, Hiesang Sohn^c, Jung Yeon Won^a, Yong Su Kim^a, JaeGwan Chung^a, Sung Heo^a, Seong Heon Kim^a, Minsu Seol^d,*, and Weon Ho Shin^e,*

E-mail: Minsu.seol@samsung.com & whshin@kicet.re.kr



Figure S1. The XPS depth profiles of C_{60} /p-type doped Gr structures ((a) Au 4f and (b) Cl 2p of C_{60} /AuCl₃_Gr, (c) F 1s of C_{60} /TFSI_Gr and N 1s of C_{60} /HNO₃_Gr structures), all of which underwent an aging process of one month under ambient conditions.



Figure S2. The UPS depth profiles of (a) C_{60}/As_Gr , (b) $C_{60}/AuCl_3_Gr$, (c) C_{60}/HNO_3_Gr and (d) $C_{60}/TFSI_Gr$ obtained after an aging process of one month under ambient conditions.



Figure S3. The XPS depth profiles of C_{60} /p-type doped Gr structures ((a) Au 4f and (b) Cl 2p of C_{60} /AuCl₃_Gr, (c) F 1s of C_{60} /TFSI_Gr and N 1s of C_{60} /HNO₃_Gr structures), all of which underwent an aging process of two months under ambient conditions.



Figure S4. The XPS depth profiles of C_{60} /p-type doped Gr structures ((a) Au 4f and (b) Cl 2p of C_{60} /AuCl₃_Gr, (c) F 1s of C_{60} /TFSI_Gr and N 1s of C_{60} /HNO₃_Gr structures), all of which underwent an aging process of three months under ambient conditions.